

Title (en)  
DEVICE FOR THERMALLY TREATING SUBSTRATES

Title (de)  
VORRICHTUNG ZUR THERMISCHEN BEHANDLUNG VON SUBSTRATEN

Title (fr)  
DISPOSITIF DE TRAITEMENT THERMIQUE DE SUBSTRATS

Publication  
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Application  
**EP 11708696 A 20110214**

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Abstract (en)  
[origin: WO2011098295A1] The invention relates to an inner heat treatment chamber (3) for thermally processing a substrate (20), comprising walls (10) that surround an inner space (24) of the inner heat treatment chamber (3), a storage unit (8) for storing the substrate (20) during the thermal processing and an energy source (11) for introducing energy into the inner space (24) of the inner heat treatment chamber (3), wherein at least a part of the inner sides of the walls (10) is designed to reflect power introduced by the energy source (11). The at least one part of the inner sides of the walls (10) is made of a material that reflects at least infrared radiation to a high degree. The invention further relates to an inner heat treatment chamber (3) for thermally processing a substrate (20), comprising walls (10) that surround an inner space (24) of the inner heat treatment chamber (3), a storage unit (8) for storing the substrates (20) during the thermal processing and an energy source (11) for introducing energy into the inner space (24) of the inner heat treatment chamber, wherein a cooling device (14) is provided for cooling the walls (10).

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